

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	IS&R	L1	2	(("6224679") or ("6364762")) .PN.	US- PGPUB ; USPAT	2006/01/2 7 11:17
2	BRS	L2	16	("4660464" "4693173" "4723480" "4813846" "5217501" "5344615" "5435683" "5553496" "5671764" "5697759" "5829939" "5833726" "5980684" "6097469") .PN. OR ("6364762") .URPN .	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:09
3	BRS	L3	22	("5551984" "5562383" "5565034" "5609459" "5626820" "5752985" "5909994" "5944894" "6017395" "6053058" "6120584") .PN. OR ("6224679") .URPN .	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:09
4	BRS	L4	17	(1 2 3) and (contaminate contaminated contaminant)	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:10

Smg

	Type	L #	Hits	Search Text	DBs	Time Stamp
5	BRS	L5	13	(1 2 3) and (contaminate contaminated contaminant) and (particles particulate)	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:10
6	BRS	L6	5	(1 2 3) and (contaminate contaminated contaminant) and (particles particulate) and purge	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:11
7	BRS	L7	1	("6497734").URPN .	USPAT	2006/01/2 7 11:14
8	BRS	L8	14	("5019233" "5147823" "5248636" "5352248" "5380682" "5388944" "5435683" "5674786" "5925227" "6093654" "6110232" "6224679" "6254328" "6310328").PN.	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:15
9	BRS	L9	770	(substrate semiconductor wafer) and load and chamber and transfer and (robot (transfer with conveyor) automated adj2 arm swing adj arm) and gas and purge	US- PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/2 7 11:19

	Type	L #	Hits	Search Text	DBs	Time Stamp
10	BRS	L1 0	542	(substrate semiconductor wafer) and load and chamber and transfer and (robot (transfer with conveyor) automated adj2 arm swing adj arm) and gas and purge and contaminat\$	US-PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/27 11:19
11	BRS	L1 1	458	(substrate semiconductor wafer) and load and chamber and transfer and (robot (transfer with conveyor) automated adj2 arm swing adj arm) and gas and purge and contaminat\$ and (particulate particles)	US-PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/27 11:45
12	BRS	L1 2	44	(substrate semiconductor wafer) and load and chamber and transfer and (robot (transfer with conveyor) automated adj2 arm swing adj arm) and gas and purge and contaminat\$ and (particulate particles) and (recirculating recirculate resupply resupplying regenerate regenerating)	US-PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/27 11:52

	Type	L #	Hits	Search Text	DBs	Time Stamp
13	BRS	L1 3	1	("2004/0168742") .URPN.	USPAT	2006/01/2 7 11:48
14	BRS	L1 4	358	(substrate semiconductor wafer) and contaminat\$ with (recirculating recirculate resupply resupplying regenerate regenerating)	US- PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/2 7 11:58
15	BRS	L1 5	5	(substrate semiconductor wafer) and contaminat\$ with purge with (recirculating recirculate resupply resupplying regenerate regenerating)	US- PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/2 7 11:59
16	BRS	L1 6	12	("3340895" "3403695" "3572366" "3973583" "4064898" "4129150" "4627465" "4958659" "5505219") .PN.	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:58
17	BRS	L1 7	12	("3340895" "3403695" "3572366" "3973583" "4064898" "4129150" "4627465" "4958659" "5505219") .PN.	US- PGPUB ; USPAT ; USOCR	2006/01/2 7 11:59

	Type	L #	Hits	Search Text	DBs	Time Stamp
18	BRS	L1 8	64	(substrate semiconductor wafer) and contaminat\$ and purge with (recirculating recirculate resupply resupplying regenerate regenerating)	US-PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/27 12:03
19	BRS	L1 9	3	("6610123").URPN .	USPAT	2006/01/27 12:00
20	BRS	L2 0	20	("2735964" "3172747" "3804942" "3988131" "4354858" "4471395" "4597781" "4684510" "4902316" "5055115" "5123936" "6042637" "6242347" "6395073" "6428611" "6450117" "6472326").PN.	US-PGPUB ; USPAT ; USOCR	2006/01/27 12:01
21	BRS	L2 1	1	(substrate and transfer and robot and contaminat\$ and purge with (recirculating recirculate resupply resupplying regenerate regenerating)).c lm.	US-PGPUB ; USPAT ; USOCR ; EPO; JPO; DERWE NT	2006/01/27 12:03

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